

In the Specification

At page 1, after the title insert:

CROSS REFERENCE TO RELATED APPLICATION

This patent application is a Continuation Application of U.S. Patent Application Serial No. 09/652,534 filed August 31, 2000, entitled "Plasma Enhanced Chemical Vapor Deposition Methods and Semiconductor Processing Methods of Forming Layers and Shallow Trench Isolation Regions," naming Sujit Sharan and Gurtej S. Sandhu as inventors, the disclosure of which is incorporated herein by reference.